

Photomask Assembly and Method for Protecting
the Same from Contaminants Generated During
Lithography Process

Inventor(s): Xun Zhang et al.

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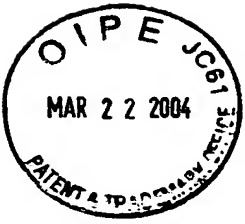


FIG. 1

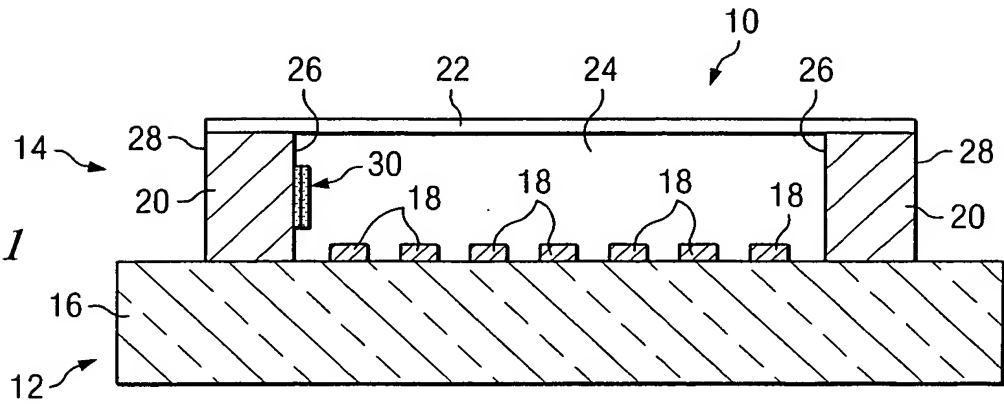


FIG. 2

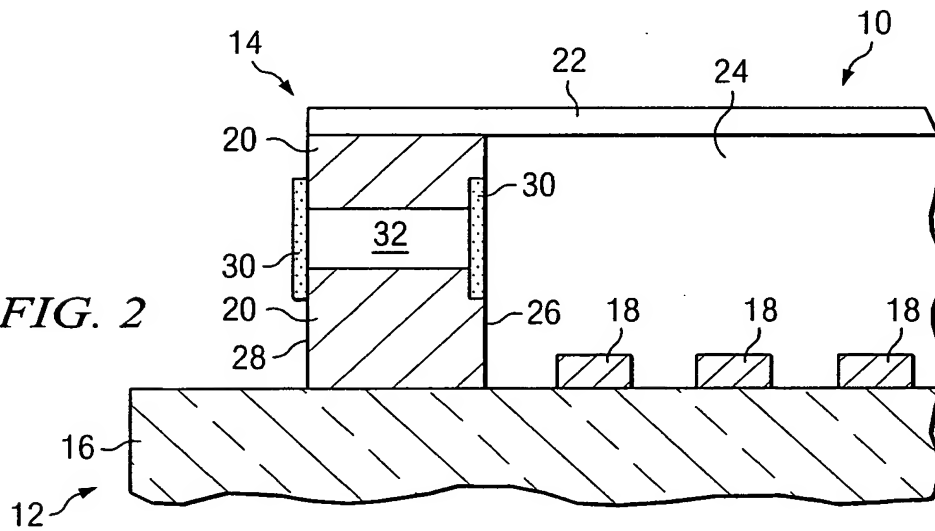


FIG. 3

